

矽化鎳在積體電路應用上之材料性質與製程技術

**Material Properties and Process  
Technologies of Nickel Silicide  
Relevant To VLSI Applications**

研究生：王超群

Student : Chao-Chun Wang

指導教授：陳茂傑

Advisor : Mao-Chieh Chen



A Dissertation

Submitted to Department of Electronics Engineering  
and Institute of Electronics  
College of Electrical Engineering and Computer Science  
National Chiao-Tung University  
In Partial Fulfillment of the Requirements  
for the Degree of  
Doctor of Philosophy  
in Electronics Engineering  
2004  
Hsinchu, Taiwan, Republic of China

中華民國九十三年十月